

| | Type | L # | Hits | Search Text | DBs | Time Stamp | C o m m e n t s | E r r o r D e f i n i t i o n | E r r o r s |
|---|------|-----|-------|---|---|---------------------|--------------------------------------|---|----------------------------|
| 1 | BRS | L1 | 0 | clean\$3 same ("polyoeyethylene butyphel ether") | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:19 | | | 0 |
| 2 | BRS | L2 | 783 | clean\$3 same ("polyoeyethylene butylphenyl ether") or(polyoxyethylene with phenyl with sulfate) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:20 | | | 0 |
| 3 | BRS | L3 | 16 | clean\$3 same (("polyoeyethylene butylphenyl ether") or (polyoxyethylene with phenyl with sulfate)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:24 | | | 0 |
| 4 | BRS | L4 | 0 | "20020202852" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:24 | | | 0 |
| 5 | BRS | L5 | 2 | "20020102852" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:38 | | | 0 |
| 6 | BRS | L6 | 62192 | thermal with (anneal\$3 or (cvd or "chemicl vapor deposition") or (oxidation)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:40 | | | 0 |
| 7 | BRS | L7 | 38560 | 6 and semiconductor | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:40 | | | 0 |
| 8 | BRS | L8 | 101 | thermal with (anneal\$3 with (cvd or "chemicl vapor deposition") with (oxidation)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:40 | | | 0 |

| | Type | L # | Hits | Search Text | DBs | Time Stamp | C o m m e n t s | E r r o r s | E r r o r s |
|----|------|-----|------|---------------------|---|---------------------|--------------------------------------|----------------------------|----------------------------|
| 9 | BRS | L9 | 98 | 8 and semiconductor | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:41 | | | 0 |
| 10 | BRS | L10 | 40 | 9 and @pd<=20000626 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/17 19:41 | | | 0 |